IN THE CLAIMS:

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Claims 1-13 (Canceled)

14. (Original) A method of treating porous dielectric materials comprising:

treating the surface of a porous dielectric material with hydrocarbon plasma, so as to deposit a carbon-rich polymer material on the surface of the porous dielectric material; and

depositing a barrier material over the carbon-rich polymer material, so as to line the vias and the trenches.

- 15. (Original) The method of claim 14, wherein the barrier material is comprised of tantalum.
- 16. (Original) The method of claim 14, wherein the barrier material is comprised of tantalum nitride.
- 17. (Original) The method of claim 14, wherein the hydrocarbon plasma is comprised of C₂H₄.
- 18. (Original) The method of claim 14, wherein the porous dielectric material is polymer material.
- 19. (Original) The method of claim 14, wherein the porous dielectric material is a non-organic material.

Claims 20-26 (Canceled)